

## TRANSMITTAL

Electronic Version v1.1

Stylesheet Version v1.1.0

<b>Title of Invention</b>	Improved Cobalt Silicidation Process for Substrates with a Silicon Germanium Layer	
Application Number :		
Date :		
First Named Applicant:	Chien-Chao Huang	
Confirmation Number:		
Attorney Docket Number:	2001.1531/24061.439	
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Submitted By:		Elec. Sign.
Mrs. Wei Wei Jeang Registered Number: 33,305		/Wei Wei Jeang/ Sign. Capacity Attorney

Documents being submitted:	Files
us-request	tsmc439-usrequ.xml us-request.dtd us-request.xsl
us-fee-sheet	tsmc439-usfees.xml us-fee-sheet.xsl us-fee-sheet.dtd
application-body	Document2-trans.xml us-application-body.xsl application-body.dtd wipo.ent mathml2.dtd mathml2-qname-1.mod isoamsa.ent isoamsb.ent isoamsc.ent isoamsn.ent isoamso.ent isoamsr.ent isogr3.ent isomfrk.ent isomopf.ent isomscr.ent isotech.ent isobox.ent isocyr1.ent isocyr2.ent isodia.ent isolat1.ent isolat2.ent isonum.ent isopub.ent mmlextra.ent mmlalias.ent soextblx.dtd fig.tif sh1.tif sh2.tif sh3.tif sh4.tif sh5.tif sh6.tif sh7.tif sh8.tif sh9.tif
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